

| Ref # | Hits | Search Query  | DBs  | Default Operator | Plurals | Time Stamp       |
|-------|------|---|--|------------------|---------|------------------|
| L1    | 4    | ((carbon near silicon near oxide) SiOCH) with methylsilsequioxane           | US-PGPUB;<br>USPAT;<br>USOCR;<br>EPO; JPO;<br>DERWENT<br>; IBM_TDB | OR               | ON      | 2005/07/27 14:58 |
| L2    | 15   | ((carbon near silicon near oxide) SiOCH) and methylsilsequioxane            | US-PGPUB;<br>USPAT;<br>USOCR;<br>EPO; JPO;<br>DERWENT<br>; IBM_TDB | OR               | ON      | 2005/07/27 14:58 |
| S1    | 0    | (carbon near silicon near oxide) with ((silicon Si) near CH2)               | US-PGPUB;<br>USPAT;<br>USOCR;<br>EPO; JPO;<br>DERWENT<br>; IBM_TDB | OR               | ON      | 2005/07/22 13:37 |
| S2    | 0    | (carbon near silicon near oxide) and ((silicon Si) near CH2)                | US-PGPUB;<br>USPAT;<br>USOCR;<br>EPO; JPO;<br>DERWENT<br>; IBM_TDB | OR               | ON      | 2005/07/22 13:35 |
| S3    | 0    | (carbon near silicon near oxide) and ((silicon Si) near CH\$1 near bond\$3) | US-PGPUB;<br>USPAT;<br>USOCR;<br>EPO; JPO;<br>DERWENT<br>; IBM_TDB | OR               | ON      | 2005/07/22 13:36 |
| S4    | 364  | (carbon near silicon near oxide)  | US-PGPUB;<br>USPAT;<br>USOCR;<br>EPO; JPO;<br>DERWENT<br>; IBM_TDB | OR               | ON      | 2005/07/22 13:41 |
| S5    | 82   | ((silicon Si) near CH\$1 near bond\$3)                                      | US-PGPUB;<br>USPAT;<br>USOCR;<br>EPO; JPO;<br>DERWENT<br>; IBM_TDB | OR               | ON      | 2005/07/27 11:01 |
| S6    | 3    | SiOCH with ((silicon Si) near CH\$1 near bond\$3)                           | US-PGPUB;<br>USPAT;<br>USOCR;<br>EPO; JPO;<br>DERWENT<br>; IBM_TDB | OR               | ON      | 2005/07/22 13:37 |
| S7    | 535  | (carbon near silicon near oxide) SiOCH                                      | US-PGPUB;<br>USPAT;<br>USOCR;<br>EPO; JPO;<br>DERWENT<br>; IBM_TDB | OR               | ON      | 2005/07/27 14:55 |

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| S8  | 3   | S7 and S5  | US-PGPUB;<br>USPAT;<br>USOCR;<br>EPO; JPO;<br>DERWENT<br>; IBM_TDB | OR | ON | 2005/07/22 13:42 |
| S9  | 3   | ("6171770"   "6329017"   "6509279").PN.  | US-PGPUB;<br>USPAT;<br>USOCR                                       | OR | ON | 2005/07/22 14:10 |
| S10 | 4   | ("4868336"   "6074962"   "6171770"  <br>"6329017").PN.                         | US-PGPUB;<br>USPAT;<br>USOCR                                       | OR | ON | 2005/07/22 14:11 |
| S11 | 6   | ("4868096"   "6057251"   "6159871"  <br>"6303192"   "6303525"   "6326692").PN. | US-PGPUB;<br>USPAT;<br>USOCR                                       | OR | ON | 2005/07/22 14:17 |
| S12 | 3   | S7 and (Si near CH2)   | US-PGPUB;<br>USPAT;<br>USOCR;<br>EPO; JPO;<br>DERWENT<br>; IBM_TDB | OR | ON | 2005/07/22 14:40 |
| S13 | 0   | ("2005/0006665").URPN.   | USPAT  | OR | ON | 2005/07/22 14:40 |
| S14 | 945 | (Si near CH2)  | US-PGPUB;<br>USPAT;<br>USOCR;<br>EPO; JPO;<br>DERWENT<br>; IBM_TDB | OR | ON | 2005/07/22 14:41 |
| S15 | 22  | (Si near CH2 near bond)  | US-PGPUB;<br>USPAT;<br>USOCR;<br>EPO; JPO;<br>DERWENT<br>; IBM_TDB | OR | ON | 2005/07/22 14:44 |
| S16 | 3   | S14 and S7   | US-PGPUB;<br>USPAT;<br>USOCR;<br>EPO; JPO;<br>DERWENT<br>; IBM_TDB | OR | ON | 2005/07/22 14:44 |
| S17 | 25  | ((silicon Si) near CH2 near bond\$3)   | US-PGPUB;<br>USPAT;<br>USOCR;<br>EPO; JPO;<br>DERWENT<br>; IBM_TDB | OR | ON | 2005/07/27 11:10 |
| S18 | 948 | ((silicon Si) near CH2)  | US-PGPUB;<br>USPAT;<br>USOCR;<br>EPO; JPO;<br>DERWENT<br>; IBM_TDB | OR | ON | 2005/07/27 12:53 |

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| S19 | 3     | S18 and ((carbon near silicon near oxide) SiOCH)   | US-PGPUB;<br>USPAT;<br>USOCR;<br>EPO; JPO;<br>DERWENT<br>; IBM_TDB | OR | ON | 2005/07/27 12:55 |
| S20 | 14    | S18 and ((insulat\$3 dielectric) near (layer\$1 film\$1))  | US-PGPUB;<br>USPAT;<br>USOCR;<br>EPO; JPO;<br>DERWENT<br>; IBM_TDB | OR | ON | 2005/07/27 11:58 |
| S21 | 565   | S18 and carbon   | US-PGPUB;<br>USPAT;<br>USOCR;<br>EPO; JPO;<br>DERWENT<br>; IBM_TDB | OR | ON | 2005/07/27 11:53 |
| S22 | 11    | S21 and (silicon near oxide)   | US-PGPUB;<br>USPAT;<br>USOCR;<br>EPO; JPO;<br>DERWENT<br>; IBM_TDB | OR | ON | 2005/07/27 11:53 |
| S23 | 1     | ((insulat\$3 dielectric) ADJ (layer\$1 film\$1))<br>AND carbon AND ((silicon Si) ADJ oxide)<br>AND SiOCH AND (Si NEAR CH2) AND<br>bond\$3.CLM. | US-PGPUB;<br>USPAT   | OR | ON | 2005/07/27 12:02 |
| S24 | 535   | ((carbon near silicon near oxide) SiOCH)   | US-PGPUB;<br>USPAT;<br>USOCR;<br>EPO; JPO;<br>DERWENT<br>; IBM_TDB | OR | ON | 2005/07/27 12:14 |
| S25 | 7     | S24 and CH2  | US-PGPUB;<br>USPAT;<br>USOCR;<br>EPO; JPO;<br>DERWENT<br>; IBM_TDB | OR | ON | 2005/07/27 12:16 |
| S26 | 12379 | ((silicon Si) near CH\$1)  | US-PGPUB;<br>USPAT;<br>USOCR;<br>EPO; JPO;<br>DERWENT<br>; IBM_TDB | OR | ON | 2005/07/27 12:34 |
| S27 | 15    | S26 and ((carbon near silicon near oxide) SiOCH)   | US-PGPUB;<br>USPAT;<br>USOCR;<br>EPO; JPO;<br>DERWENT<br>; IBM_TDB | OR | ON | 2005/07/27 12:35 |

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| S28 | 4947 | (silicon Si) near ("CH.sub.2" CH2)  | US-PGPUB;<br>USPAT;<br>USOCR;<br>EPO; JPO;<br>DERWENT<br>; IBM_TDB | OR | ON | 2005/07/27 12:54 |
| S29 | 8    | S28 and ((carbon near silicon near oxide)<br>SiOCH)   | US-PGPUB;<br>USPAT;<br>USOCR;<br>EPO; JPO;<br>DERWENT<br>; IBM_TDB | OR | ON | 2005/07/27 12:55 |
| S30 | 8    | ("3615913"   "3895429"   "5116495"  <br>"5128737"   "5205902"   "5298587"  <br>"5320875"   "5575929").PN. | US-PGPUB;<br>USPAT;<br>USOCR                                       | OR | ON | 2005/07/27 13:03 |

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|-------|-------|---|--|------------------|---------|------------------|
| L1    | 55586 | interconnect\$3 near (layer\$1 film\$1 line\$1)                         | US-PGPUB;<br>USPAT;<br>USOCR;<br>EPO; JPO;<br>DERWENT<br>; IBM_TDB | OR               | ON      | 2005/07/27 17:55 |
| L2    | 3926  | 1 and (interlayer near (insulat\$3 dielectric) near (layer\$1 film\$1)) | US-PGPUB;<br>USPAT;<br>USOCR;<br>EPO; JPO;<br>DERWENT<br>; IBM_TDB | OR               | ON      | 2005/07/27 17:56 |
| L3    | 900   | 2 and (diffus\$3 near (layer film))                                     | US-PGPUB;<br>USPAT;<br>USOCR;<br>EPO; JPO;<br>DERWENT<br>; IBM_TDB | OR               | ON      | 2005/07/27 17:57 |
| L4    | 192   | 3 and damascene   | US-PGPUB;<br>USPAT;<br>USOCR;<br>EPO; JPO;<br>DERWENT<br>; IBM_TDB | OR               | ON      | 2005/07/27 18:01 |
| L5    | 149   | 4 and (SiO (silicon adj oxide))   | US-PGPUB;<br>USPAT;<br>USOCR;<br>EPO; JPO;<br>DERWENT<br>; IBM_TDB | OR               | ON      | 2005/07/27 18:01 |

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|-------|------|--|--|------------------|---------|------------------|
| L1    | 2799 | (Cu copper) near contain\$3 near (metal Si Al Ag W Mg Be Zn Pd Cd Au Hg Pt Zr Ti Sn Ni Fe) | US-PGPUB;<br>USPAT;<br>USOCR;<br>EPO; JPO;<br>DERWENT<br>; IBM_TDB | OR               | ON      | 2005/07/28 07:13 |
| L2    | 187  | 1 and damascene  | US-PGPUB;<br>USPAT;<br>USOCR;<br>EPO; JPO;<br>DERWENT<br>; IBM_TDB | OR               | ON      | 2005/07/28 07:14 |